

Notice of References Cited	Application/Control No. 10/719,083		Applicant(s)/Patent Under Reexamination HWANG ET AL.	
	Examiner Patricia A. George		Art Unit 1765	Page 1 of 3

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	B	US-6,190,824	02-2001	Fukushige et al.	430/163
*	C	US-6,261,721	07-2001	Andrieu et al.	429/249
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	K	US-			
	L	US-			
	M	US-			

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NON-PATENT DOCUMENTS

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*	V	Shibata et al. of Material and Process Development of Tri-level Resist System in KrF and ArF Lithography [Proc. SPIE Vol. 4690, July 2002, Advances in Resist Technology and Processing XIX;
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.